



An XML-Based Approach to Integrating Semiconductor Process Information

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Northrop Grumman Corp.

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Outline

•Project motivation

- Need to integrate data archiving and simulation activities in collaborative semiconductor processing research

•XML

- Overview
- Use in representing wafer processing data

•Applications

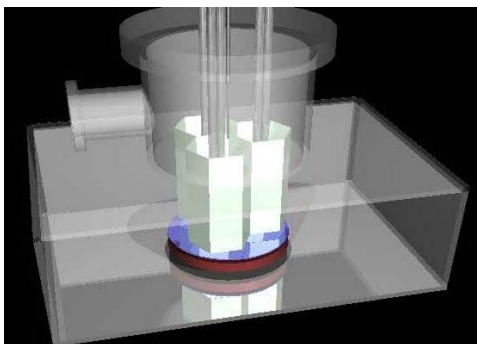
- Java
- MATLAB

www.isr.umd.edu/Labs/CACSE/IT

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Spatially programmable equipment – A new design paradigm for semiconductor processing equipment

- Joint research with G. W. Rubloff;
- A new concept in semiconductor manufacturing intended to address limited sensing and control capabilities of current chemical vapor deposition processes;
- Main design innovation: segmented showerhead with individual control of gas composition/flow and sampling at each segment.

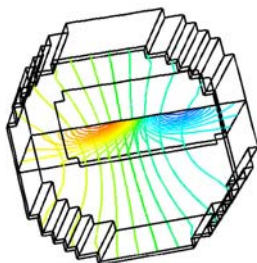
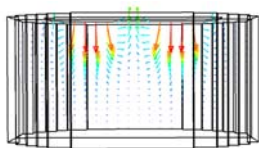


www.isr.umd.edu/Labs/CACSE/research/progrxr

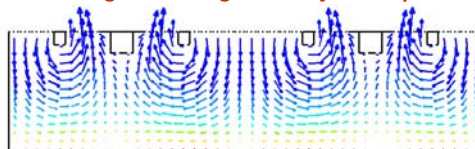
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Segmented showerhead design

2 Segment Reactor *Velocity & Conc*



N Segment Design *Velocity & Temp*

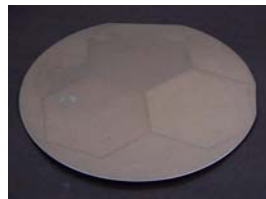
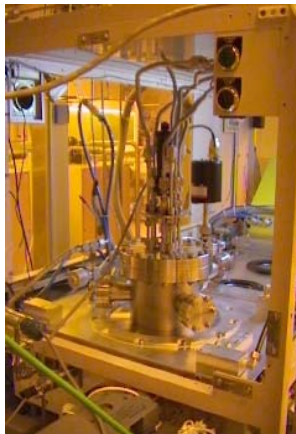


- Periodic gas flow fields minimize inter-segment convective transport;
- Inter-segment region mass transfer is governed by diffusion, making much better control of across-wafer gas composition;
- Residual gas can be sampled from each segment, simplifying spatial composition measurements

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Spatially programmable equipment – IT issues

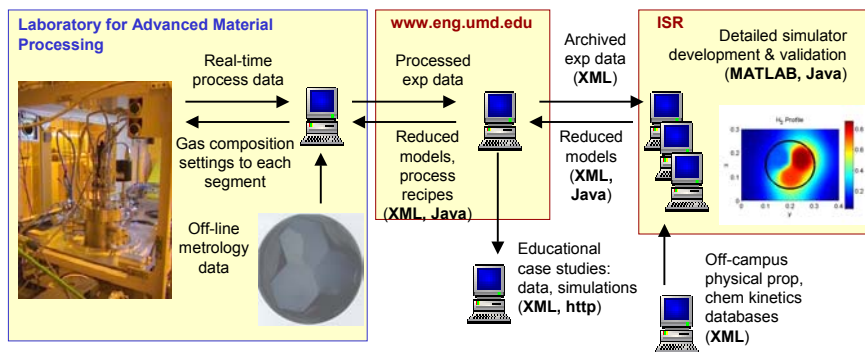
- 3-zone prototype is running;
- First films deposited have demonstrated that spatially patterned wafers can be produced by controlling gas phase composition;
- Large amount of heterogeneous data types, incomplete data sets;
- Significant simulation research is needed to understand prototype and materials produced by prototype.



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Programmable CVD reactor data archiving/analysis

1. XML for representing experimental data;
2. Java parser methods called from a MATLAB application;
3. Java and MATLAB methods for data analysis.



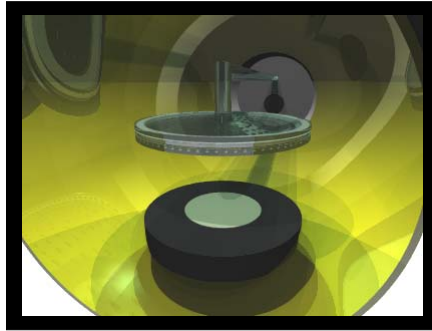
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GaN MOCVD reactor design

Potential IT Issues

- Joint collaboration between University of Maryland and Northrop Grumman Electronic Systems research groups at separate research facilities;
- CVD reactor design has followed iterative simulator development and experimental evaluation cycles;
- Elements UMD/NG simulators can be shared;
- Secure transfer of proprietary data.



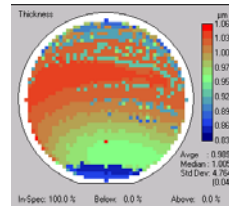
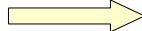
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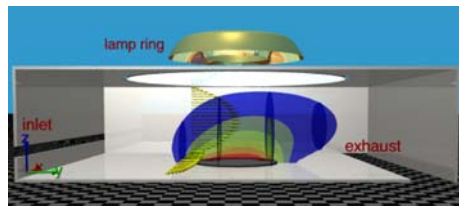
Iterative simulation-based design of CVD systems



CVD process operations leading to spatially non-uniform film growth



Simulation-based assessment of design and operation alternatives



Object-oriented CVD simulation tools for diagnosing factors responsible for non-uniformity

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What is XML?

- XML: eXtensible Markup Language
- Generic syntax to mark up data with human readable tags in plain text format
- Standard format for computer documents, flexible enough to be customized for various data interchange applications (user-defined tags)
- Hierarchical tree-like data structure
- Validation against Document Type Declaration
- Separation of data representation and presentation/use

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Semiconductor experimental data structure

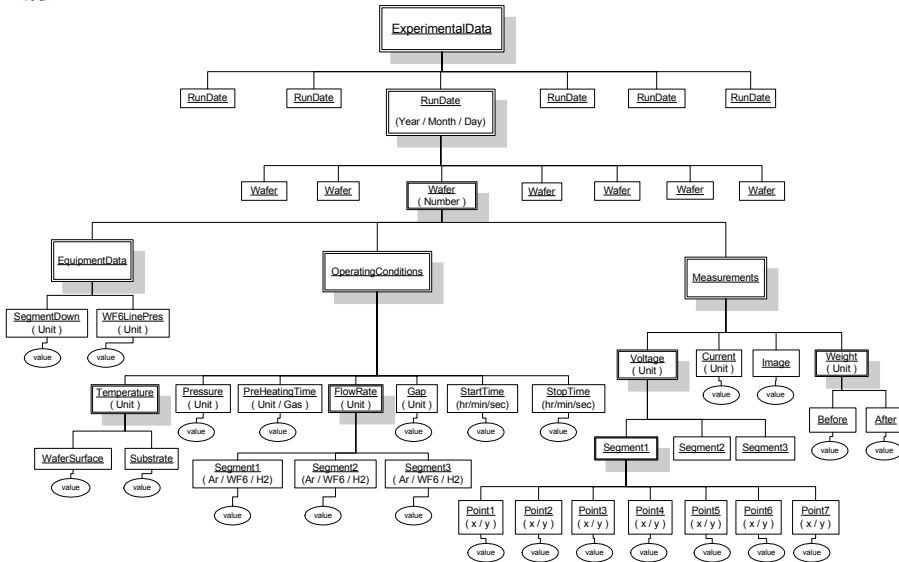
Wafer number: w100102-03



- EquipmentData (*process diagnosis*)
 - Gas line pressure
 - Wafer position
- OperatingConditions data (*simulator input*)
 - Wafer/segment spacing
 - Segment gas flows
- Measurements data (*analysis, simulator validation*)
 - Initial wafer mass
 - Final wafer mass
 - Sheet resistance profiles

- Structure influenced by use
- Store raw data only

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```

<?xml version="1.0" ?>
<!-- moredata.xml -->
<!-- XML format experimental data of wafer -->
<!-- Fall, 2002 -->
<!DOCTYPE ExperimentalData (View Source for full doctype...)>
<ExperimentalData>
  <RunDate year="2002" month="09" day="12">
    <Wafer number="w091202-04">
      <EquipmentData>
      <OperatingConditions>
        <Temperature unit="C">
          <WaferSurface>300</WaferSurface>
          <Substrate>400</Substrate>
        </Temperature>
        <Pressure unit="torr">0.5</Pressure>
        <PreHeatingTime unit="min" gas="HF">5</PreHeatingTime>
        <Gap unit="mm">1</Gap>
        <FlowRate unit="sccm">
          <Segment1F Ar="50" WF6="0" H2="0" />
          <Segment2F Ar="50" WF6="0" H2="0" />
          <Segment3F Ar="50" WF6="0" H2="50" />
        </FlowRate>
      </OperatingConditions>
    </Wafer number>
  </RunDate>
</ExperimentalData>

```

Document begins with declaration that specifies XML version 1.0

Comments

Document type definition (DTD) defines document structure and entities

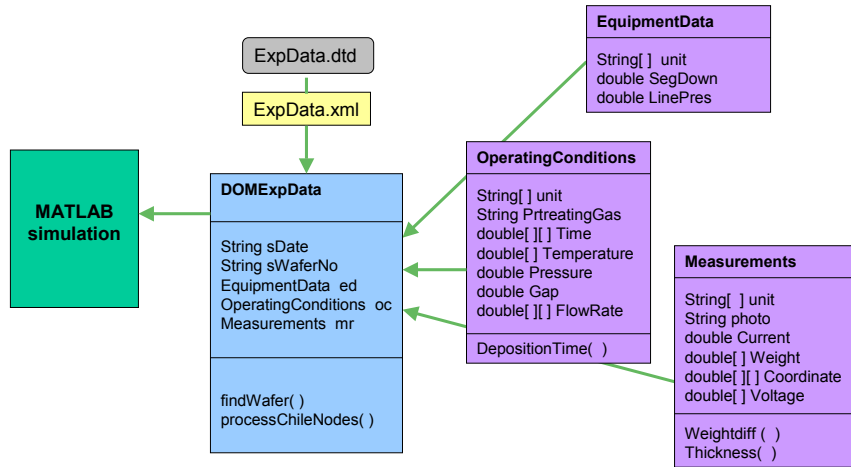
Element RunDate contains three attributes: year, month and day

Root element ExperimentalData contains child element(s) RunDate

Child elements of element Temperature

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Using the archived data



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Reading data into a MATLAB session - Java methods

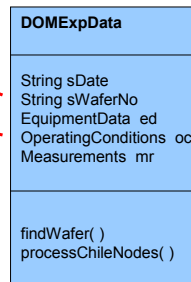
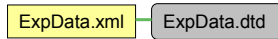
```

% download and parse XML; create Java object
url = java.net.URL('http://www.isr.umd.edu/Labs/CACSE/A_team/IT/xml/PRdata.xml');
WJO = DOMmoredata(url, 'w091202-06');

% display wafer number (Java object public field)
Wnumber = WJO.sWaferNo

% Java OperatingConditions object
JOC = WJO.oc;
% Java method to compute deposition time
dtime = JOC.DepTime

% Java Measurements object
JMR = WJO.mr;
% Java method to compute net mass gain
dmass = JMR.WeightDiff
    
```



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```

OperatingConditions
String[] unit
String PrtreatingGas
double[][] Time
double[] Temperature
double Pressure
double Gap
double[][] FlowRate
DepositionTime()

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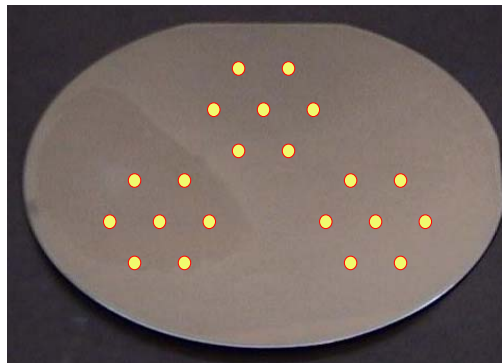
Measurements
String[] unit
String photo
double Current
double[] Weight
double[][] Coordinate
double[] Voltage
Weightdiff()
Thickness()

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MATLAB application: Measurements branch

```

- <Wafer number="w091202-06">
+ <EquipmentData>
+ <OperatingConditions>
- <Measurements>
  <Current unit="A">0.001</Current>
  - <Voltage unit="mV">
    - <Segment1R>
      <Point11 x="1" y="1">5.90</Point11>
      <Point12 x="2" y="1">6.91</Point12>
      <Point13 x="1" y="3">6.01</Point13>
      <Point14 x="2" y="3">4.70</Point14>
      <Point15 x="3" y="3">5.68</Point15>
  
```



•Wafer metrology data stored in OperatingConditions object after parsing

•Voltage measurements taken at 21 points on wafer surface

•Film thickness = $\rho l / (4.53 V)$

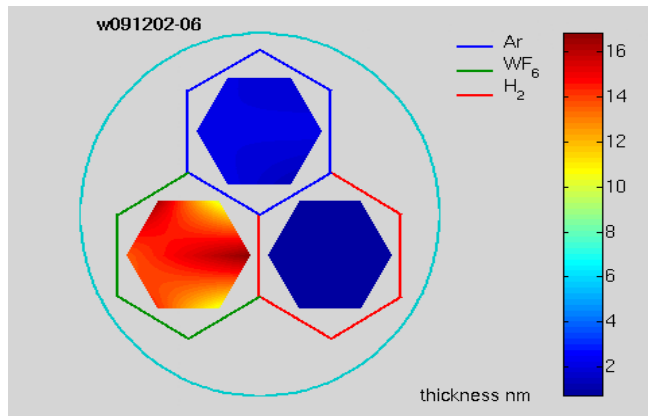
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MATLAB application: Measurements branch

•Results from MATLAB function waferPlot(WJO)

•Feed conditions:
pure Ar to segment 1, pure WF_6 to segment 2, pure H_2 to segment 3

•Q: why is W deposited in any of the segments?



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MATLAB application: Operating Conditions branch

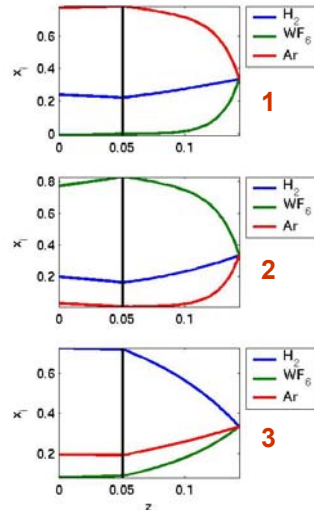
• Convert Java WJO object to MATLAB segsim (segment simulation) object



• Model transport through segments by Stefan-Maxwell equations including thermal diffusion

• Define segsim method to solve BVPs for each segment using a global spectral method (MWRtools)

• A: back-diffusion from common exhaust region to wafer surface, Si reduction by WF_6



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Conclusions

Initial success in developing an XML-based framework for on-line archiving and distributed simulation for semiconductor CVD manufacturing processes

Current work focuses on

- Simple data browsing techniques
- Integrating additional data: mass spec time traces, wafer maps, images, etc.
- Representing equipment design information suitable for simulators
- Thermo-physical property estimators
- Surface and gas phase reaction kinetics